FIG. 1

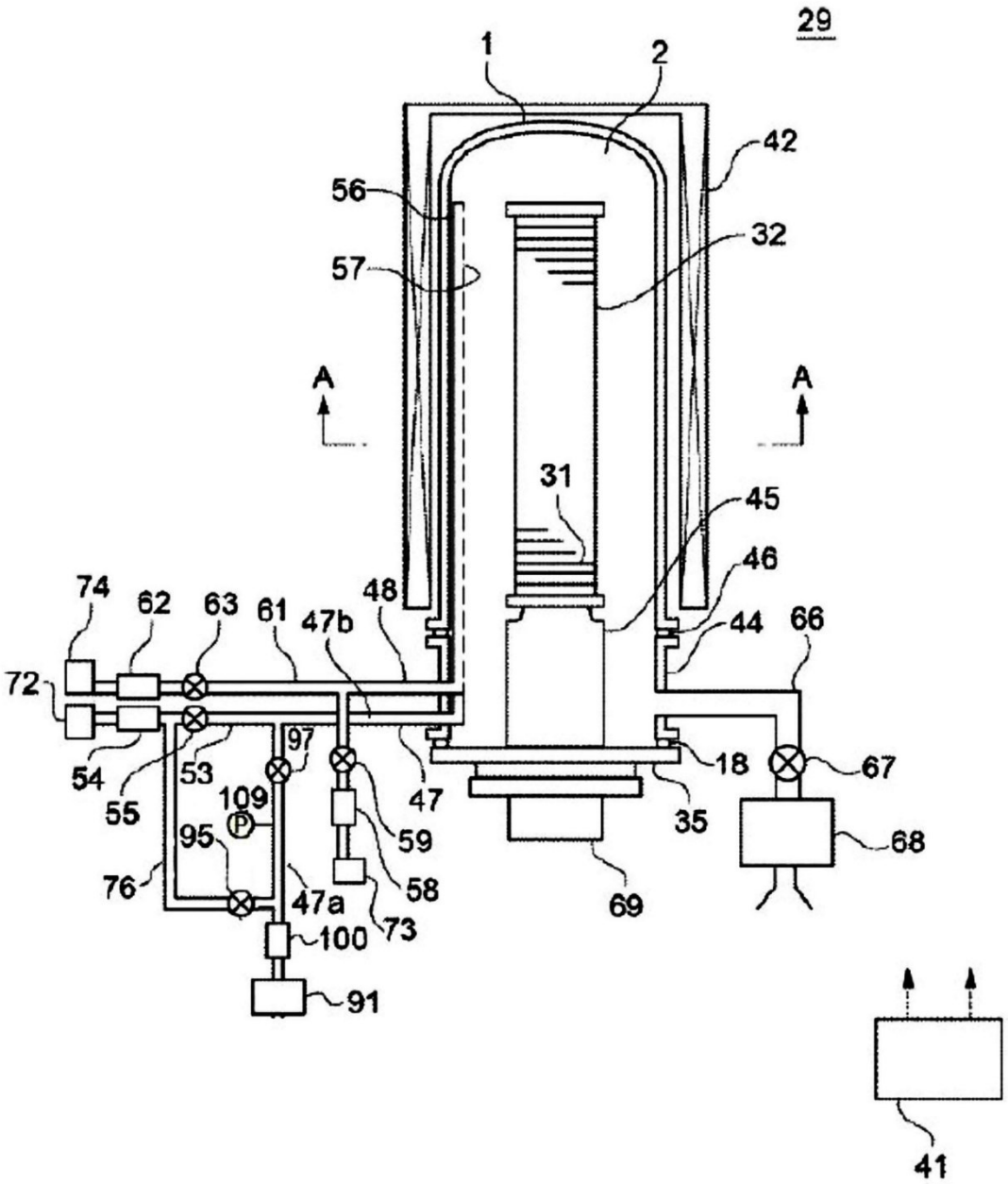

29
1
2
42
56
32
57
A
A
31
45
46
74
62
63
61
47b
48
44
66
72
97
18
67
54
53
55
109
47
35
95
59
68
76
47a
58
69
73
100
91
41

FIG. 2

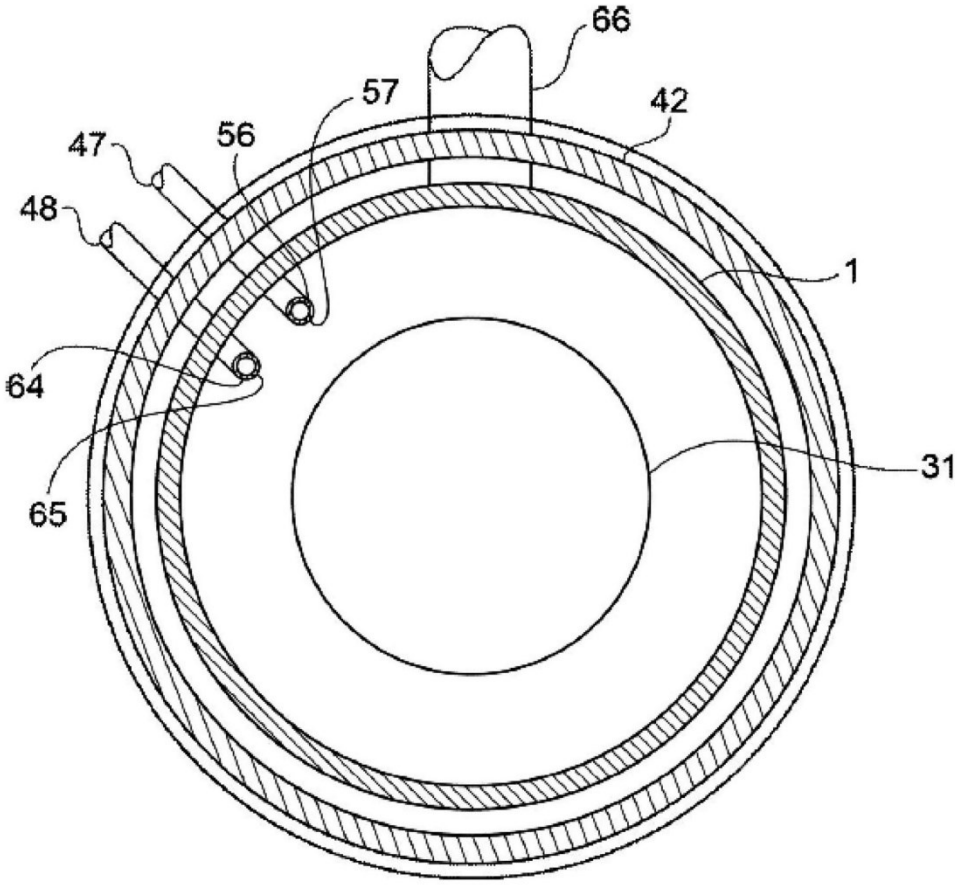


FIG. 3

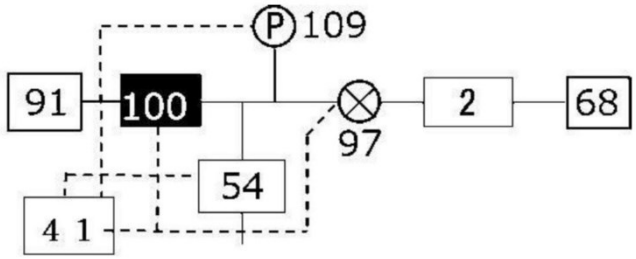


FIG. 4

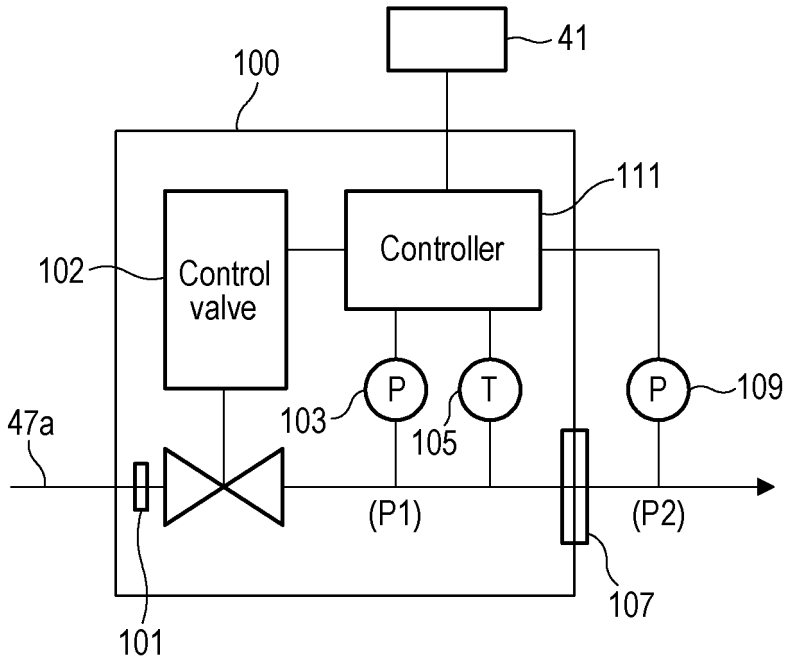

41
100
111
102
Control valve
Controller
P
T
P
109
103
105
47a
(P1)
(P2)
101
107

FIG. 5

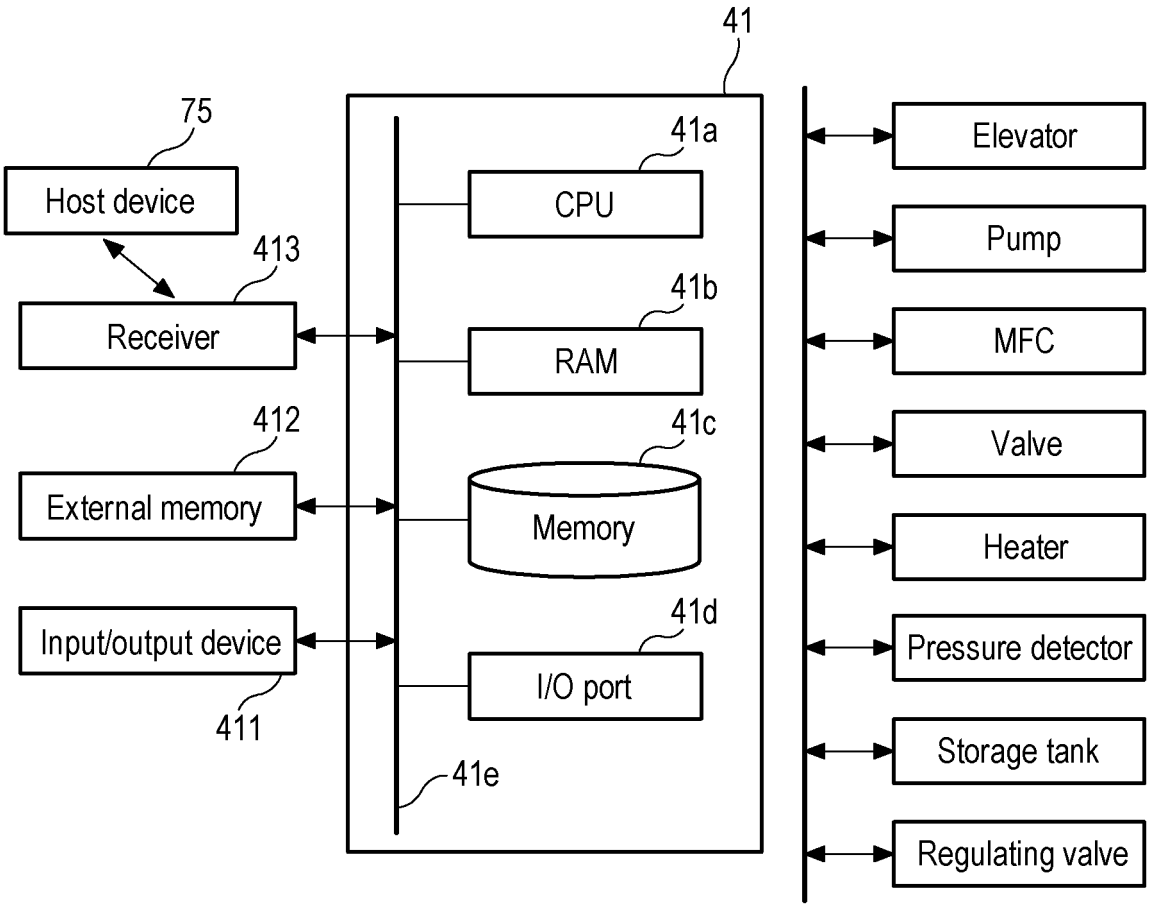

41
75
Host device
413
Receiver
412
External memory
Input/output device
411
41a
CPU
41b
RAM
41c
Memory
41d
I/O port
41e
Elevator
Pump
MFC
Valve
Heater
Pressure detector
Storage tank
Regulating valve

FIG. 6

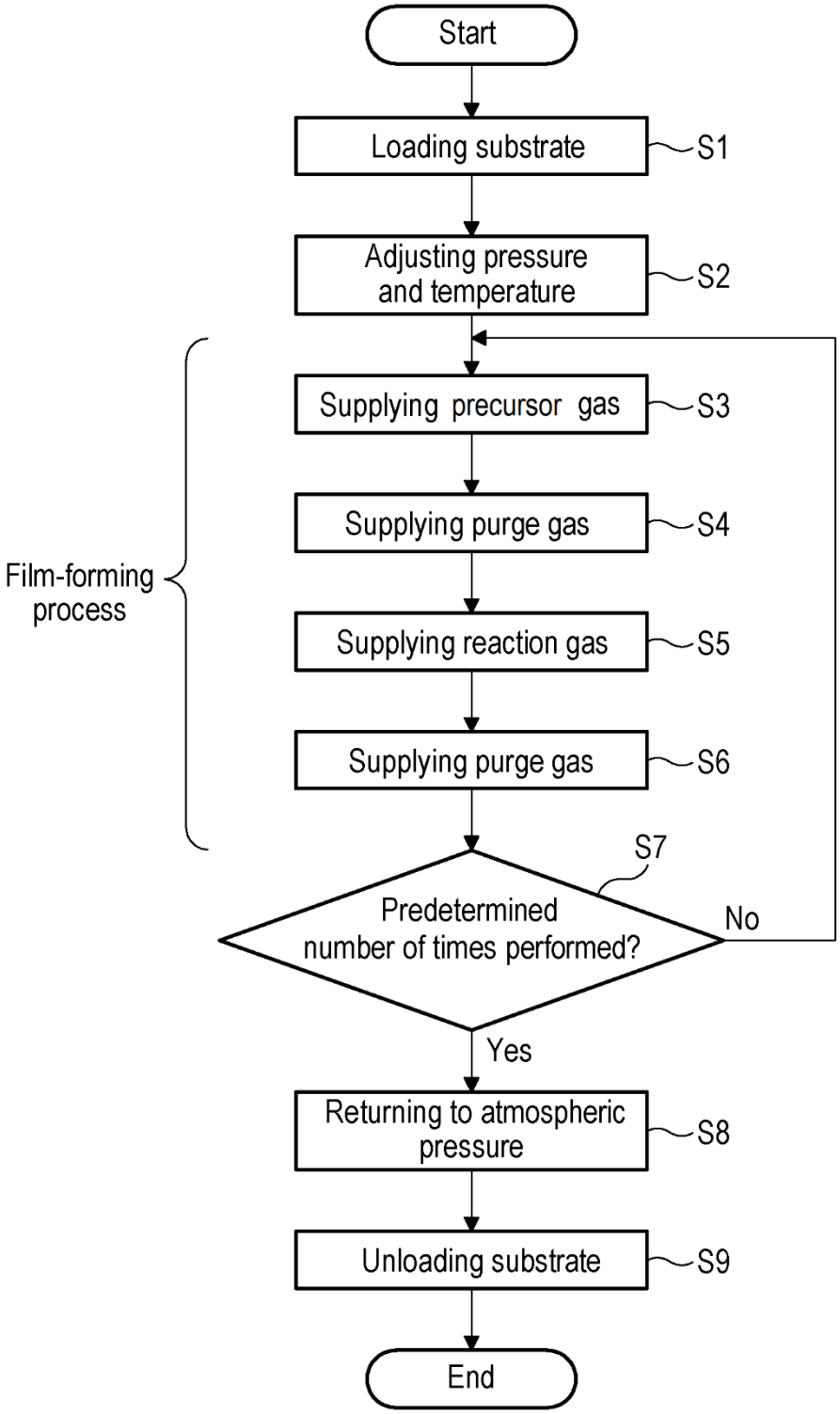

Start
Loading substrate
S1
Adjusting pressure and temperature
S2
Supplying precursor gas
S3
Supplying purge gas
S4
Supplying reaction gas
S5
Supplying purge gas
S6
Film-forming process
S7
Predetermined number of times performed?
No
Yes
Returning to atmospheric pressure
S8
Unloading substrate
S9
End

FIG. 7

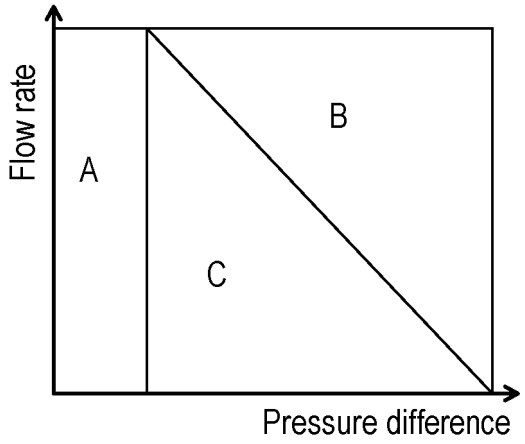


FIG. 8

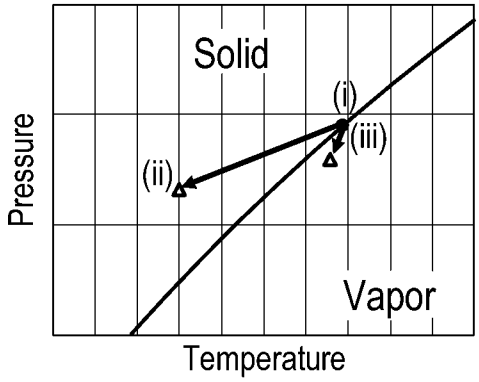


FIG. 9

